

<b>INFORMATION DISCLOSURE STATEMENT</b>	Atty. Docket No.: 150.00840102	Serial No.: 10/770,797
	Applicant(s): Yates et al.	Confirmation No.: Unassigned
	Application Filing Date: February 3, 2004	Group: Unassigned
	Information Disclosure Statement mailed:	April 26, 2004

**U.S. PATENT DOCUMENTS**

Examiner Initial	Copy Enclosed	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
<i>mr</i>		3,968,565	07/13/76	Bertens et al.			
		5,545,289	08/13/96	Chen et al.			
		5,741,368	04/21/98	Sahbari			
		5,780,359	07/14/98	Brown et al.			
		5,811,022	09/22/98	Savas et al.			
		5,851,302	12/22/98	Solis			
		5,876,903	03/02/99	Ng et al.			
		5,891,803	04/06/99	Gardner			
		6,063,712	05/16/00	Gilton et al.			
		6,162,738	12/19/00	Chen et al.			
<i>mr</i>		6,703,319	03/09/04	Yates et al.			

**FOREIGN PATENT DOCUMENTS**

Examiner Initial	Copy Enclosed	Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
<i>mr</i>		0662705 A2	12/29/94	Europe				
<i>l</i>		0773480 A1	11/13/96	Europe				
		411067703	03/9/99	Japan				
<i>mr</i>		WO 99/45443	09/10/99	PCT				

**OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)**

Examiner Initial	Copy Enclosed	Document Description
<i>mr</i>		"Material Safety Data Sheet for PRX-407®", Silicon Valley Chemlabs, Inc., Sunnyvale, VA 94086, 1998:4 pgs.

EXAMINER	Date Considered
<i>mr</i>	5/24/07

\*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609: Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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	Application Filing Date: February 3, 2004	Group: Unassigned
	Information Disclosure Statement mailed: April <u>26</u> , 2004	

Examiner Initial	Copy Enclosed	Document Description
		"Material Safety Data Sheet", Shipley, <i>PRX-407 Advanced Plasma Etch Polymer Remover</i> , July 26, 2000:7 pgs.
		Product information for: PRX-407 <sup>®</sup> Advanced Plasma Etch Polymer Remover, Silicon Valley Chemlabs, Inc., Sunnyvale, CA 94086, 1998
		"Post-Etch SWP Removal," SVC Silicon Valley Chemlabs, Inc., Sunnyvale, CA 94086:5 pgs.
		"Product Selection Guide," SVC Silicon Valley Chemlabs, Inc., Sunnyvale, CA 94086:2 pgs
		Sotoaka et al., "Cleaning solvent for manufacturing semiconductor element and semiconductor element using the same," English Abstract of JP 411067703 A:1 pg.

<b>EXAMINER</b>	<b>Date Considered</b>
<small>*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>	

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<b>INFORMATION DISCLOSURE STATEMENT</b>	Atty. Docket No.: 150.00840102	Serial No.: 10/770,797
	Applicant(s): Yates et al.	Confirmation No.: 1476
	Application Filing Date: February 3, 2004	Group: 1751
	Information Disclosure Statement mailed:	February 28, 2007

## U.S. PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
		None					

## FOREIGN PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
M	X	WO 98/40338	17 September 1998	PCT				

## OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)

Examiner Initial	Copy Enclosed	Document Description
		None

EXAMINER



Date Considered

5/24/07

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